



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of
Kazuyuki NITTA et al.
Serial No. 09/987,718
Filed November 15, 2001

METHOD FOR FORMING A HOLE-
PATTERNEDE PHOTORESIST LAYER

: MAIL STOP AFTER FINAL
: Docket No. 2001_1703A
: Group Art Unit 1756
: Examiner K. Sagar

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RESPONSE UNDER 37. CFR 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1756

RESPONSE TO FINAL REJECTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This is in response to the Final Rejection dated November 4, 2003.